

SILICON PHOTONICS

Dries Van Thourhout / 24 October 2018 / SPICE workshop Mainz



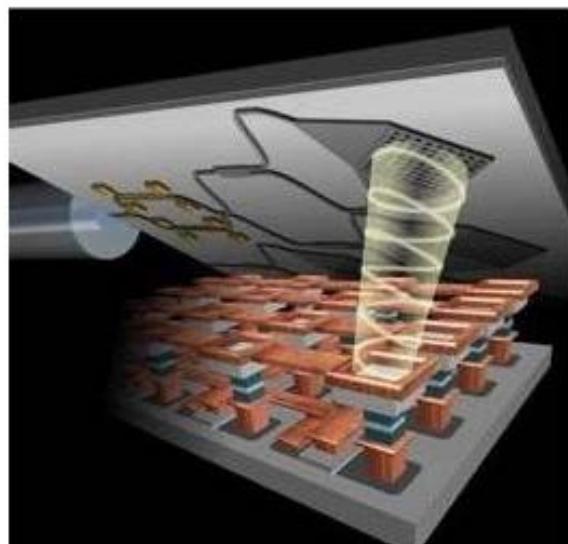
EU H2020 FET-OPEN Project

Objective: developing a **spintronic-photonic IC platform** to create world class ultra fast and low power memory and sensor designs

Silicon Photonics !

Need:

- Distribution of optical signals (passives)
- Switching of optical signals
- Coupling of optical signals



Coordinator: **Martijn Heck** (Aarhus)

Partners: Aarhus, IMEC, Spintec, Nijmegen, Quantum Wise

PHOTONICS RESEARCH GROUP

Research Group of Ghent University

- Faculty of Engineering and Architecture
- Department of Information Technology (INTEC)
- Associated laboratory of IMEC
- Member of the Center for Nano- & Biophotonics (NB photonics)

Technology Research

- Photonic Integration: Systems on a chip
- On silicon: "Silicon Photonics"
- Enhanced with new materials: III-V, ferro-electrics, graphene, ...

Applications

- High-speed telecom and datacom
- Sensing for life sciences: visible and Mid-IR
- Optical information processing

9 Professors
16 postdocs
50 PhD students
10 support staff

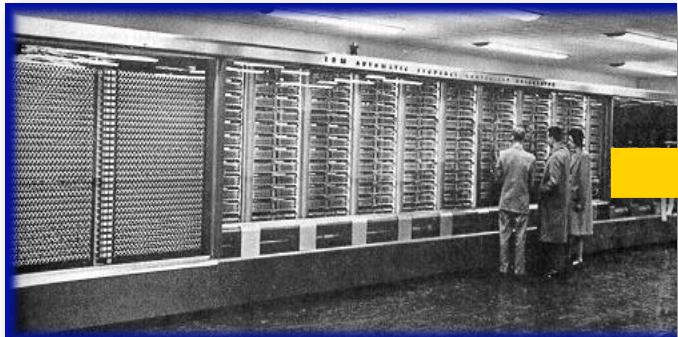
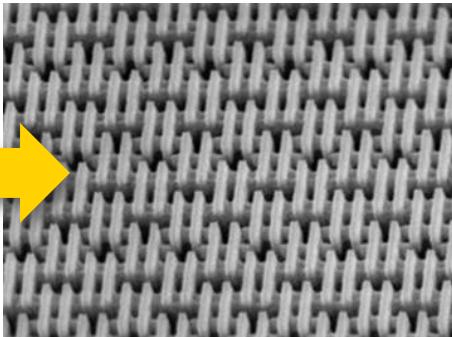
20+ nationalities
6 ERC grants
4 spin-off companies
50 journal papers/year
Class 100 clean rooms



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WHY INTEGRATED PHOTONICS ?

- In electronics: integration leads to miniaturization, higher performance, cost savings, robustness

IBM, mark 1
5 tons of components can multiply in 1 sec

Modern TSMC-chip (7nm)
Several billion transistors billions of multiplications per sec (from TSMC.com)

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WHY NOT INTEGRATED PHOTONICS ?

Electronics



Photonics

- Single building block:
 - Transistor
 - Single material:
 - Silicon
 - Relaxed processing requirements
 - Digital devices
 - High yield
 - Massive economies of scale
 - Common roadmap
-
- Many building blocks
 - Laser, Modulator, Detector Filter
 - Many technologies and materials
 - Laser : III-V semiconductors
 - Modulator : LiNbO₃
 - Filter : Glass, Polymers
 - High processing requirements
 - Analog devices
 - Low Yield
 - No economies of scale advantage
 - Many factions pushing own solution

CAN “SILICON PHOTONICS” OVERCOME THIS BOTTLENECK ?

- Single material platform
 - Silicon transparent at telecom wavelengths
 - Very high contrast : compact circuits
 - Detectors (germanium), Modulators (pn-junction)
 - Wafer level testing
- Reuse installed equipment base
 - Use best equipment available
 - Without the capital expense ...
 - Possibility to ramp up to high volumes
- Some standardization and roadmapping ongoing



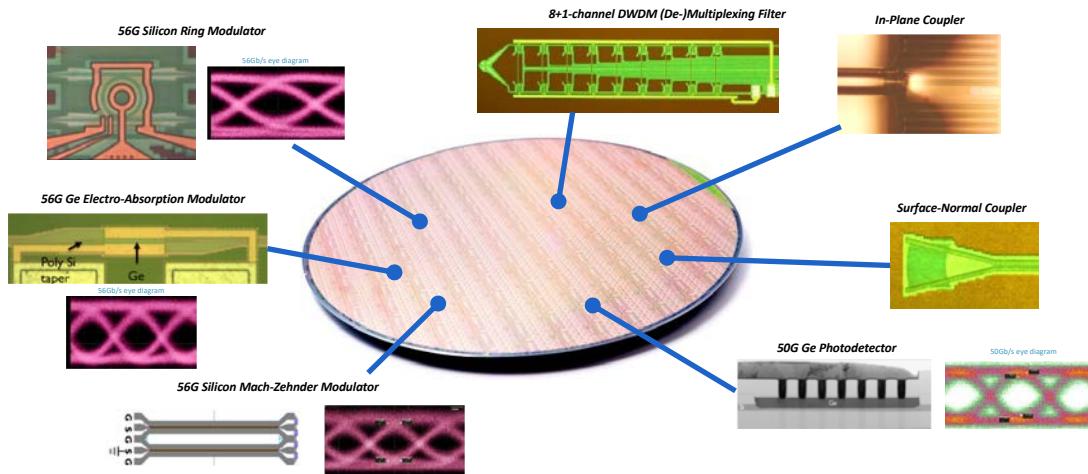
THE PAST 5-10 YEARS: STUNNING INDUSTRIAL DEVELOPMENT IN SILICON PHOTONICS FOR TELECOM AND DATACOM

- active optical cables (eg PSM4: 4x28 Gb/s on parallel fibers)
- WDM transceivers (eg 4 WDM channels x 25 Gb/s on single fiber)
- coherent receiver (eg 100 Gb/s PM-QPSK)
- fiber-to-the-home bidirectional transceiver (eg 12 x 2.5 Gb/s)
- monolithic receiver (eg 16x20Gb/s)
- 40Gb/s, 50Gb/s and 100 Gb/s Ethernet (future: 400Gb/s)
- ...



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IMEC SILICON PHOTONICS PLATFORM FULLY INTEGRATED 8X50G DWDM SI PHOTONICS TECHNOLOGY



Co-integration of the various building blocks in a single platform (O-band, C-band)

Today available on 200mm wafer size, coming soon on 300mm

95% compatible with CMOS130 in commercial foundries

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The 50G I_QO_N CW-DPDR Photonic Modulator

Transmitting a

Comparison of I_QO_N

Si CMOS Photonic

Others (Announced)

- ✓ 130nm design rules for

- ✓ 130nm design rules for

- ✓ CMOS FEOL integration (Ge-last after activation)

- ✓ Large Litho variations required

- ✓ 6mm² per transceiver

- ✓ 10x higher inter

- ✓ The only ameri

- ✓ 50channels x

- (can be)

- <http://www.research.I>

Transmit
Module



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Luxtera Product Assembly at CM Site in Asia

IBM

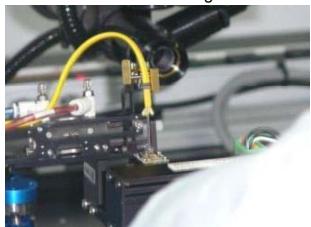
Module (Cable End) Assembly Line



Test Stations & Housing Assembly stations



Automated Fiber/Laser Alignment Tools



Shipping Production Volumes

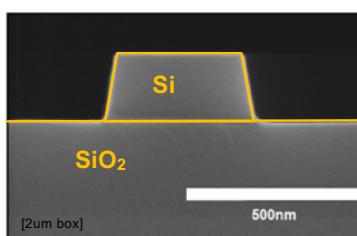
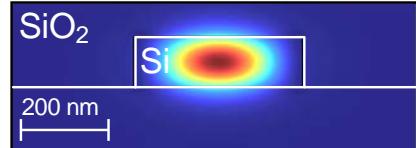


Luxtera is producing silicon photonics solutions in high-volume

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STRAIGHT WAVEGUIDE

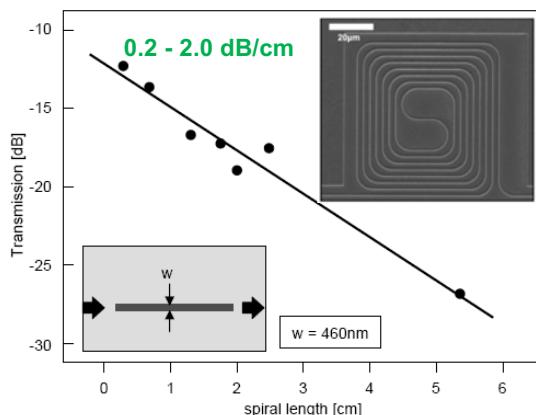
- Our standard waveguide: 450nm x 220nm Si
- Fabricated using 193nm DUV lithography
- In standard pilot line, on 200mm or 300mm wafer
- Starting from SOI or amorphous silicon



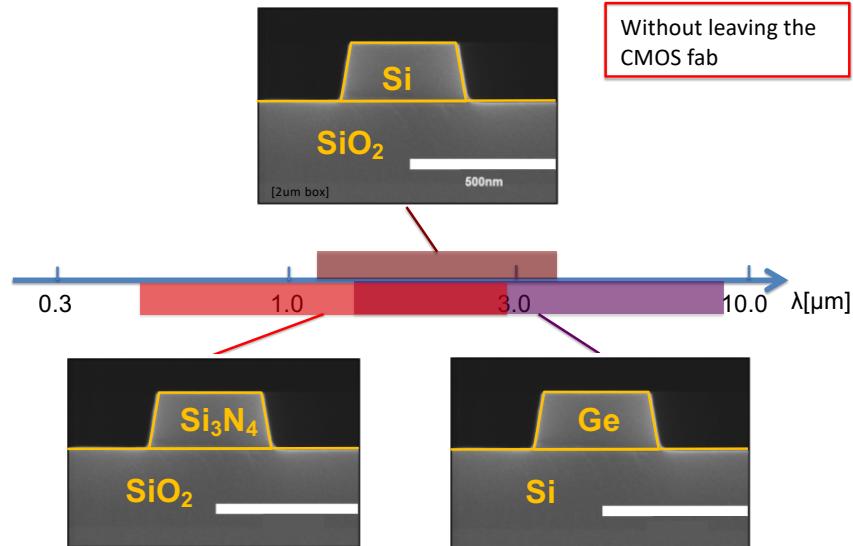
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Bogaerts e.a. , JSTQE 16, 33-44 (2010)



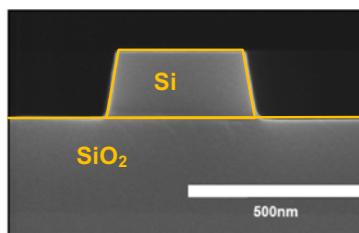
SILICON PHOTONICS: EXTENDING THE WAVELENGTH RANGE



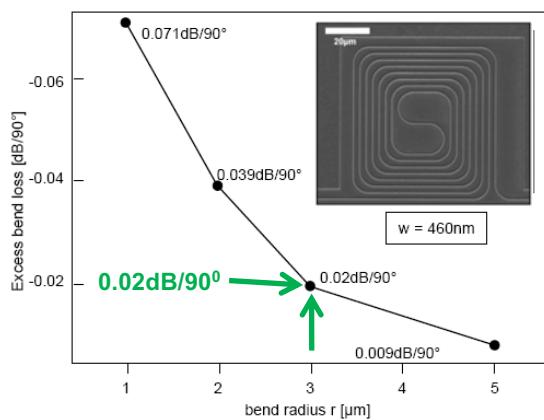
BEND WAVEGUIDE

S.K. Selvaraja, JLT 27, p.4070 (2009)
Y.A. Vlasov and S.J. McNab, Optics Express, p. 1622 (2004)

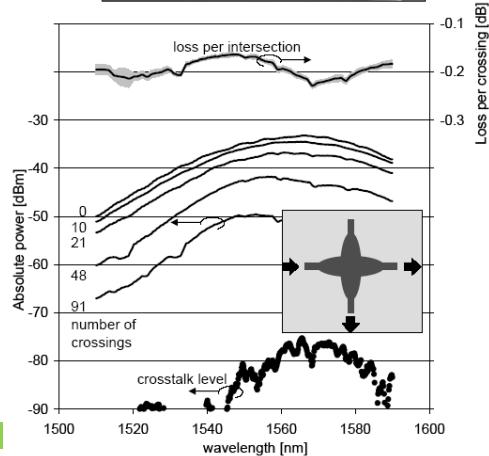
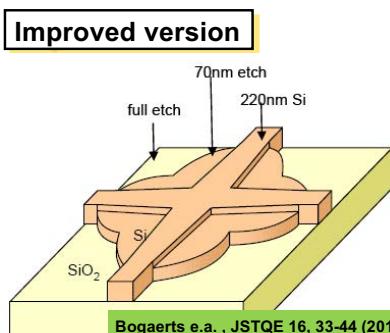
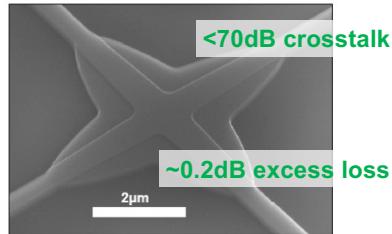
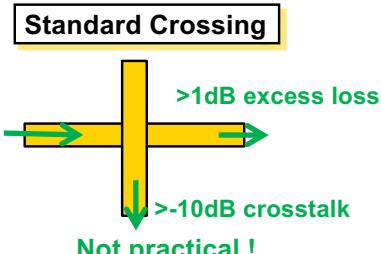
- Our standard waveguide: 450nm x 220nm Si
- Fabricated using 193nm DUV lithography
- In standard pilot line, on 200mm wafer
- Starting from SOI or amorphous silicon



- In agreement with FDTD calculations
- Offset straight-bend might improve performance (?)



CROSSINGS

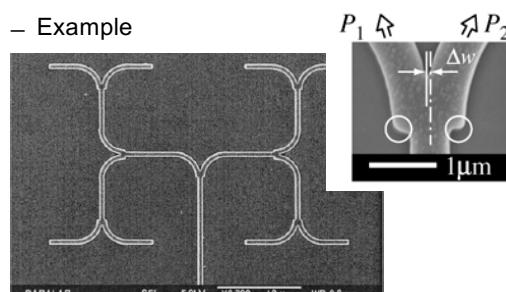


THE Y-JUNCTION

| | | |
|-----|--|----------|
| (a) | | 2.0 dB |
| (b) | | 0.5 dB |
| (c) | | 0.5 dB |
| (d) | | < 0.1 dB |
| (e) | | 0.3 dB |
| (f) | | < 0.1 dB |

Large **losses** for standard Y-junction
Need **improved** design !!!

– Example

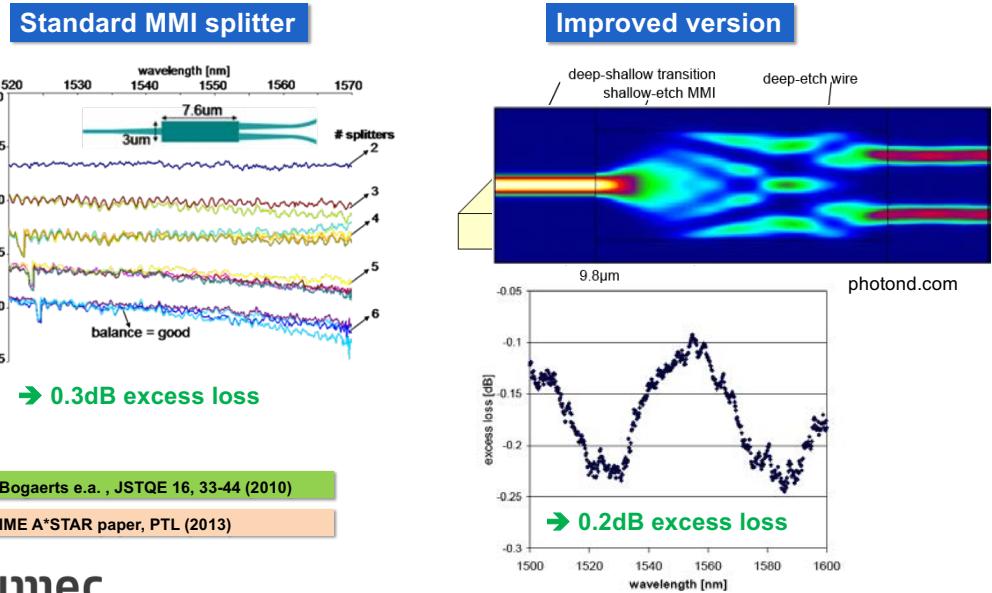


- Experiment: 0.3dB excess loss
- Some imbalance due to opt. prox. effects

Sakai e.a., IEICE Trans E85-C 1033 (2002)

Fukazawa e.a. Jpn JAP 41, p L1461 (2002)

MULTI-MODE INTERFEROMETER (MMI)

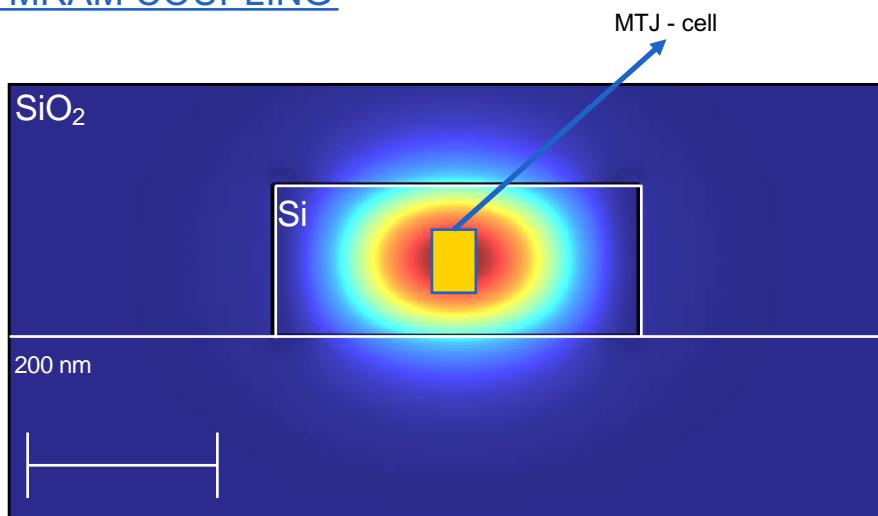


FIBER - CHIP COUPLING

We would like

- Low loss
- Broadband
- High coupling tolerance
- No facet reflections
- Waferscale testability
- Easy to fabricate
- A solution for the polarization problem

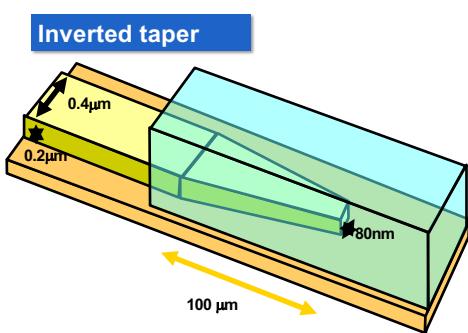
CHIP - MRAM COUPLING



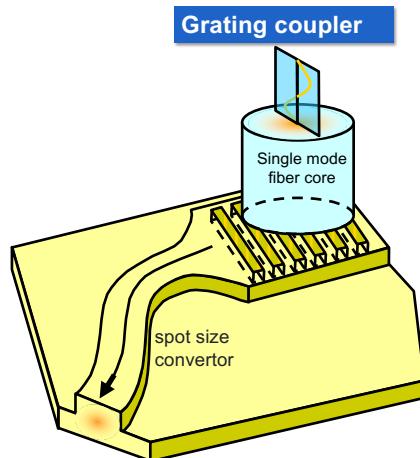
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FIBER CHIP COUPLING: TWO WIDELY USED SOLUTIONS



polished
facet

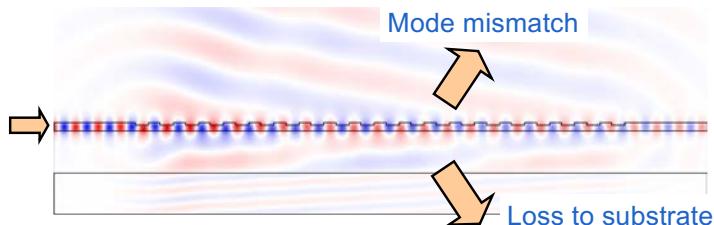


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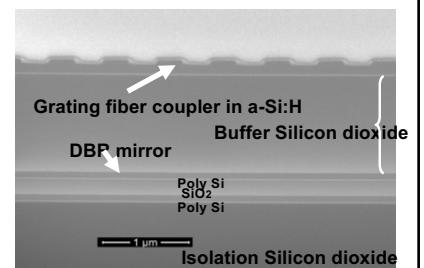
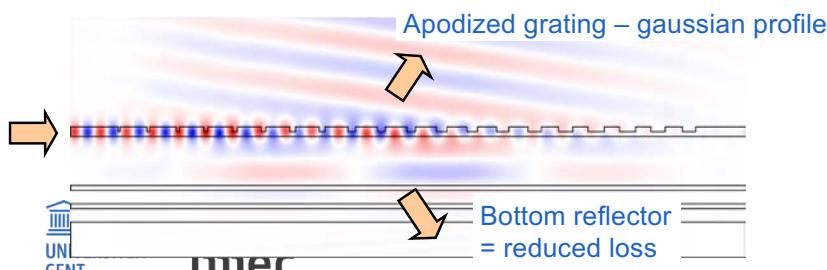
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GRATING COUPLER – OPERATING PRINCIPLE

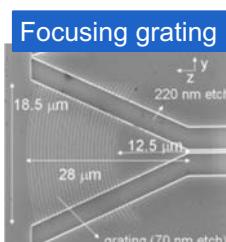
– Standard coupler (33% efficiency)



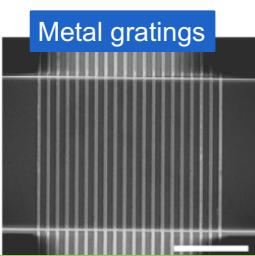
– Improved coupler (>90% efficiency)



GRATING ZOO

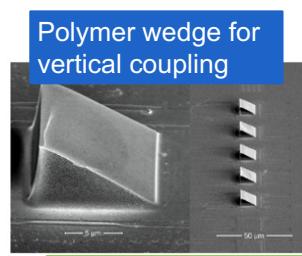


F. Van Laere, PTL 19, p. 1919 (2006)



Metal gratings

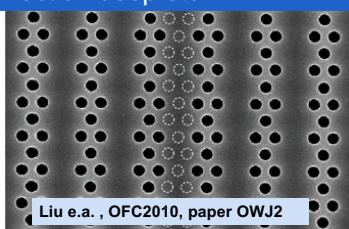
Scheerlinck, APL 92 p.031104 (2008)



Polymer wedge for vertical coupling

Schrauwen e.a. Phot. West, 7218, , p.72180B (2009)

Photonic crystal grating for low reflection deep etch

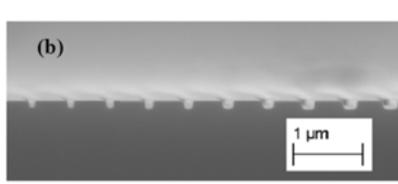


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Liu e.a. , OFC2010, paper OWJ2

Apodized grating



(b)

Tang e.a. , OFC2010, paper OWJ6

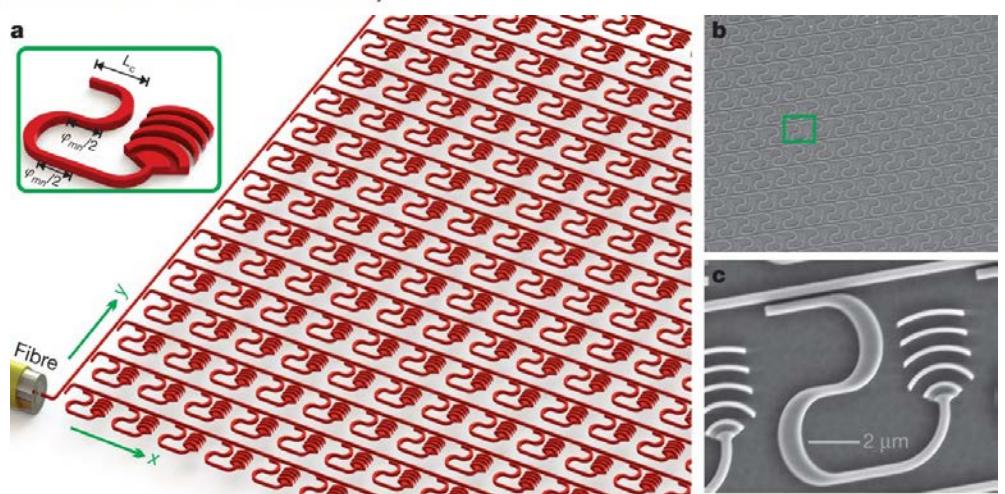
Large-scale nanophotonic phased array

Jie Sun, Erman Timurdogan, Ami Yaacobi, Ehsan Shah Hosseini & Michael R. Watts

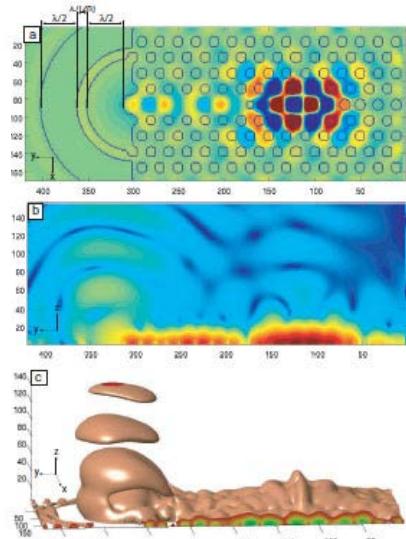
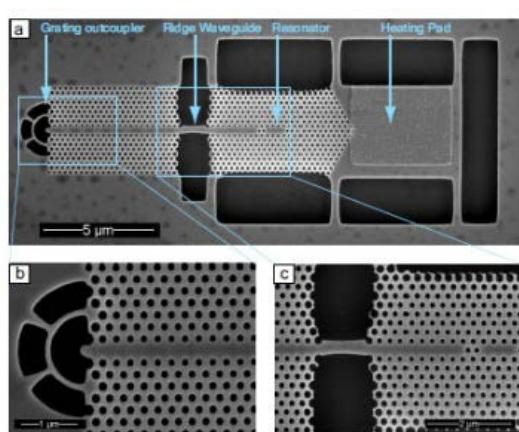
Affiliations | Contributions | Corresponding author

Nature 493, 195–199 (10 January 2013) | doi:10.1038/nature11727

Received 02 August 2012 | Accepted 29 October 2012 | Published online 09 January 2013



MINIMIZING THE OUTPUT COUPLER



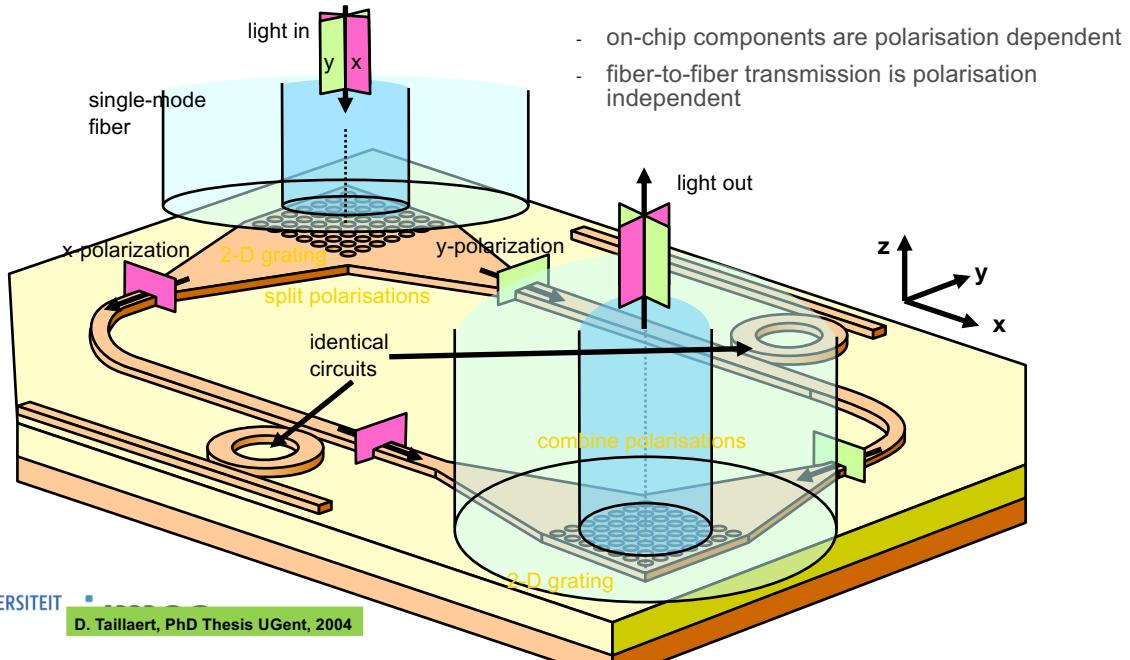
Andrei Faraon e.a., Optics Express 2008 (Stanford)



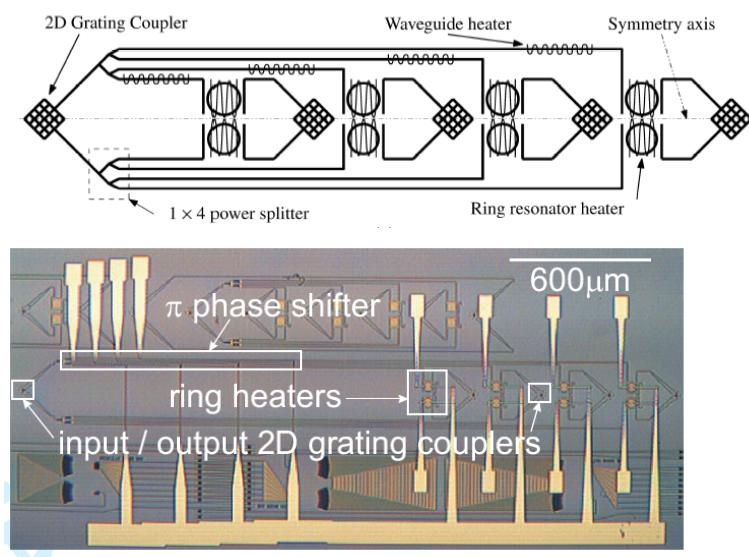
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POLARISATION DIVERSITY CIRCUIT



2D-GRATING COUPLERS ALLOW CONTROL OF POLARIZATION

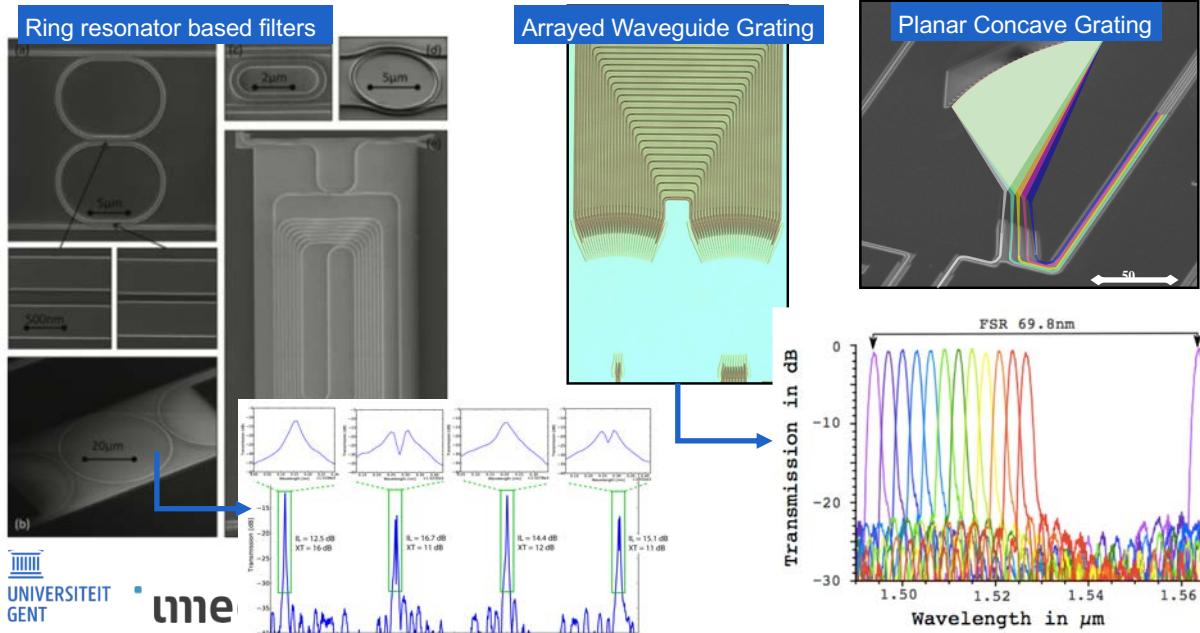


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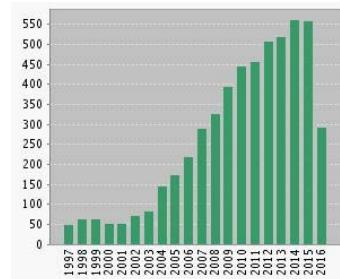
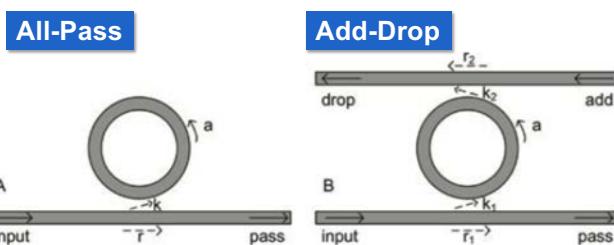
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See Halir e.a., OFC 2010, paper OWJ1

LARGE FAMILY OF PASSIVE DEVICES



RING RESONATORS



Main characteristics

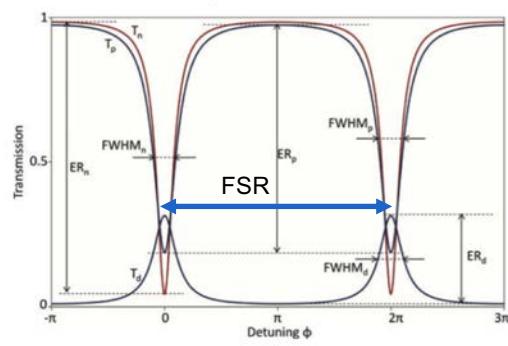
- Resonance wavelength
- Free Spectral Range (Periodicity)
- Quality Factor Q ($Q = \lambda / \Delta\lambda$)
- Finesse
- Loss ...

$$Q=1E3 \rightarrow \Delta\lambda=1.5\text{nm}$$

$$Q=1E6 \rightarrow \Delta\lambda=1.5\text{pm}$$



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Bogaerts e.a., LPR 2012
Li e.a., LPR 2016

RING RESONATORS

All-Pass

A input pass

B input - \vec{r}_1 -

Add-Drop

drop - \vec{r}_2 -

Main characteristics

- Resonance wavelength
- Free Spectral Range (Periodicity)
- Quality Factor Q ($Q = \lambda / \Delta\lambda$)
- Finesse
- Loss ...

$Q = 1E3 \rightarrow \Delta\lambda = 1.5\text{nm}$

$Q = 1E6 \rightarrow \Delta\lambda = 1.5\text{pm}$

(a)

500 nm

5 μm

(c)

2 μm

(d)

5 μm

(b)

20 μm

50 μm

RING RESONATORS

R=4.5μm

2 μm

R=1.5μm

1 μm

b

20 μm

Normalized transmission

Wavelength [nm]

fit: $Q = 15600 \pm 500$

Normalized transmission

Wavelength [nm]

$R=1.5\mu\text{m} - Q=9000$

Normalized transmission

Wavelength [nm]

Xu e.a., OE 16, pp 4309 (2008)

0.17 nm

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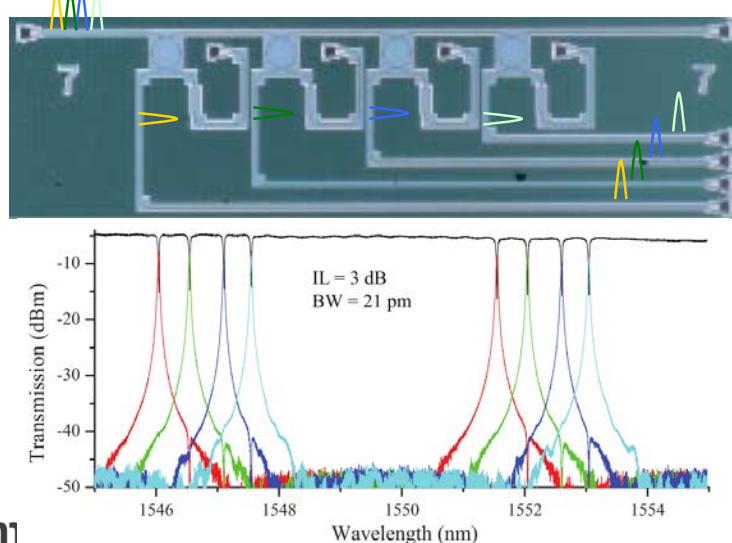
imec

Bogaerts e.a., JSTQE 16, 33-44 (2010)

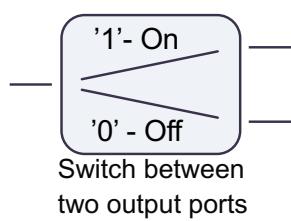
Xu e.a., OE 16, pp 4309 (2008)

THE RING RESONATOR AS WAVELENGTH DEMULTIPLEXER

→ Rings with increasing radius



SI PHOTONICS PLATFORM – SWITCHING TECHNOLOGIES

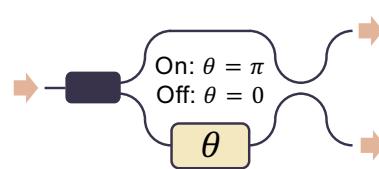


θ Optical phase shift

$$\Delta\theta = (2\pi/\lambda)\Delta n L$$

Refractive index change required!!

MZI-based
switch

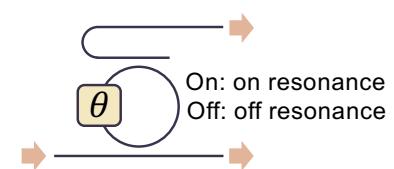


- + Bandwidth (10s of nm)
- Efficiency ($\sim mW$)

J. Van Campenhout, OpEx 17, p23793 (2009)

A. Ribeiro, OpEx 25, p29779 (2017)

Ring-resonator-based
switch



- + Efficiency ($\sim \mu W$)
- Bandwidth (<1 nm)

Q. Xu, OpEx 15, p430 (2007)

N. Sherwood-Droz, OpEx 16, p15915 (2008)



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SI PHOTONICS PLATFORM – REFRACTIVE INDEX CHANGE

Electro-Optic effect

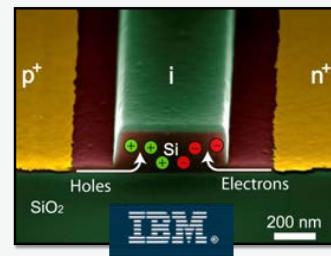
$$\begin{aligned}\Delta n_{\text{LiNbO}_3}/E &= 100 \text{ pm/V} \\ \Delta n_{\text{strained-Si}}/E &= 15 \text{ pm/V}\end{aligned}$$

LiNbO₃ - Yes
Silicon - No
(unless strained)

Plasma-Dispersion effect

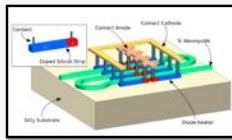
$$\begin{aligned}\Delta n_{\text{Si}}(N) &= -8.8 \times 10^{-22}N - 8.5 \times 10^{-18}N^{0.8} \\ \alpha(N) &= (8.5 \times 10^{-18} + 6 \times 10^{-18})N\end{aligned}$$

Carrier injection or
Carrier depletion



Thermo-Optic effect

$$\Delta n_{\text{Si}}/T = 1.86 \times 10^{-4} \text{ K}^{-1}$$



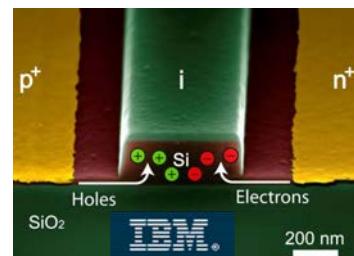
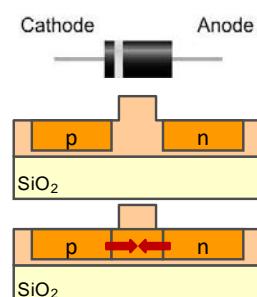
Large in Silicon (2 x LiNbO₃)
-> but slow (~100 μs)

CARRIER INJECTION TECHNOLOGY - CONCEPT

Cathode Anode

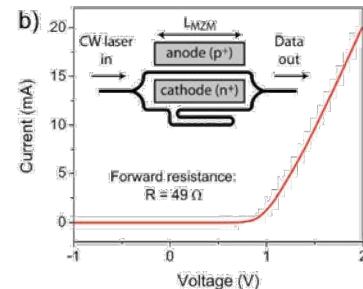
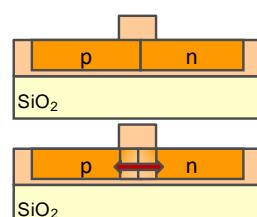
Carrier injection

- p-i-n diode in forward bias
- Inject carriers into waveguides
- Strong effect (many carriers)
- Moderate fast effect (~1 GHz)

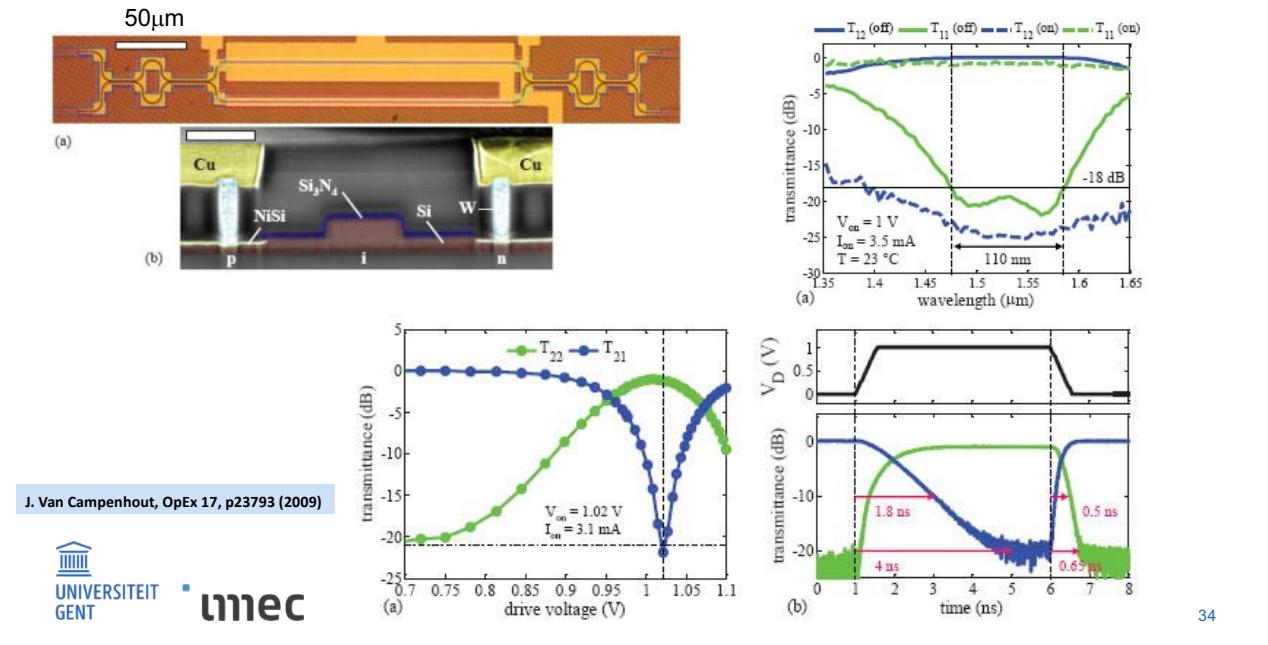


Carrier depletion

- p-n diode in reverse bias
- Extract carriers from waveguides
- Weaker effect
- Fast effect (>40 GHz)

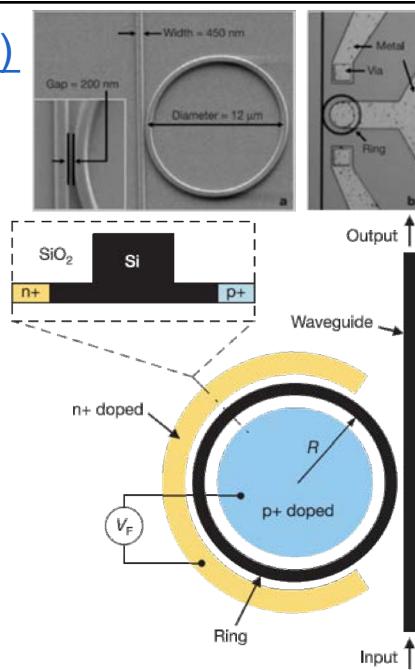
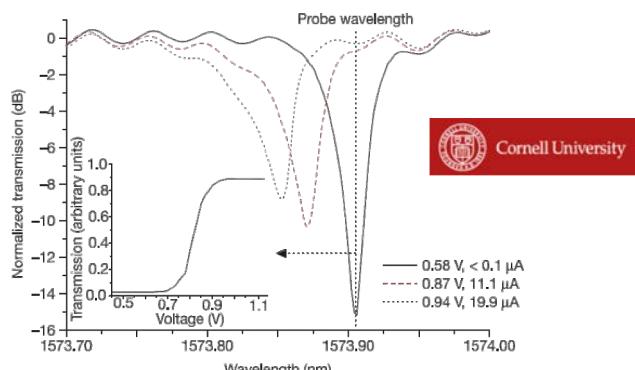


A TYPICAL MACH-ZEHNDER PIN SWITCH



INJECTION MODULATOR (RING)

- Use resonator to enhance effects
- Speed ~2GB/s
- With pre-emphasis: >20GB/s

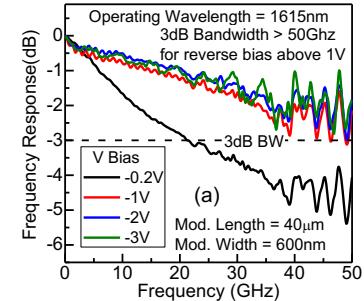
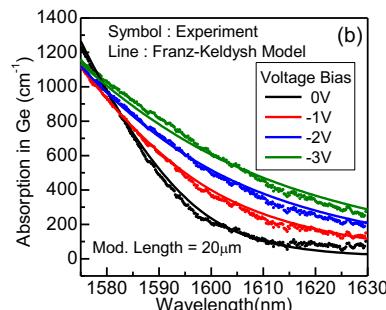
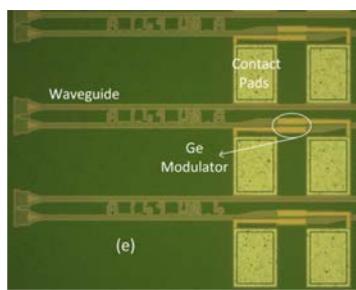
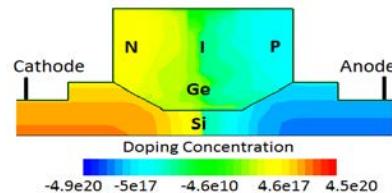


Q. Xu et al, nature 435(19), p03569 (2005)

GeSi Franz Keldysh ELECTRO-ABSORPTION MODULATOR

Advantages

- Uses existing Ge-detector technology
- Compact, optical BW > 35nm
- 3dB BW > 40GHz

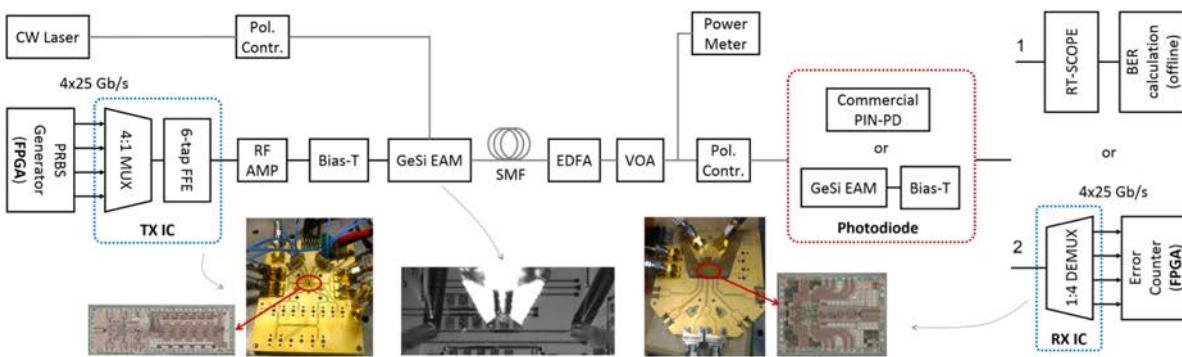


Gupta, S., et al. 50GHz Ge Waveguide Electro-Absorption Modulator Integrated in a 220nm SOI Photonic Platform. In Optical Fiber Communication Conference (Vol. 1, pp. 5–7) 2015.

RESEARCH ULTRA-HIGH-SPEED COMMUNICATION

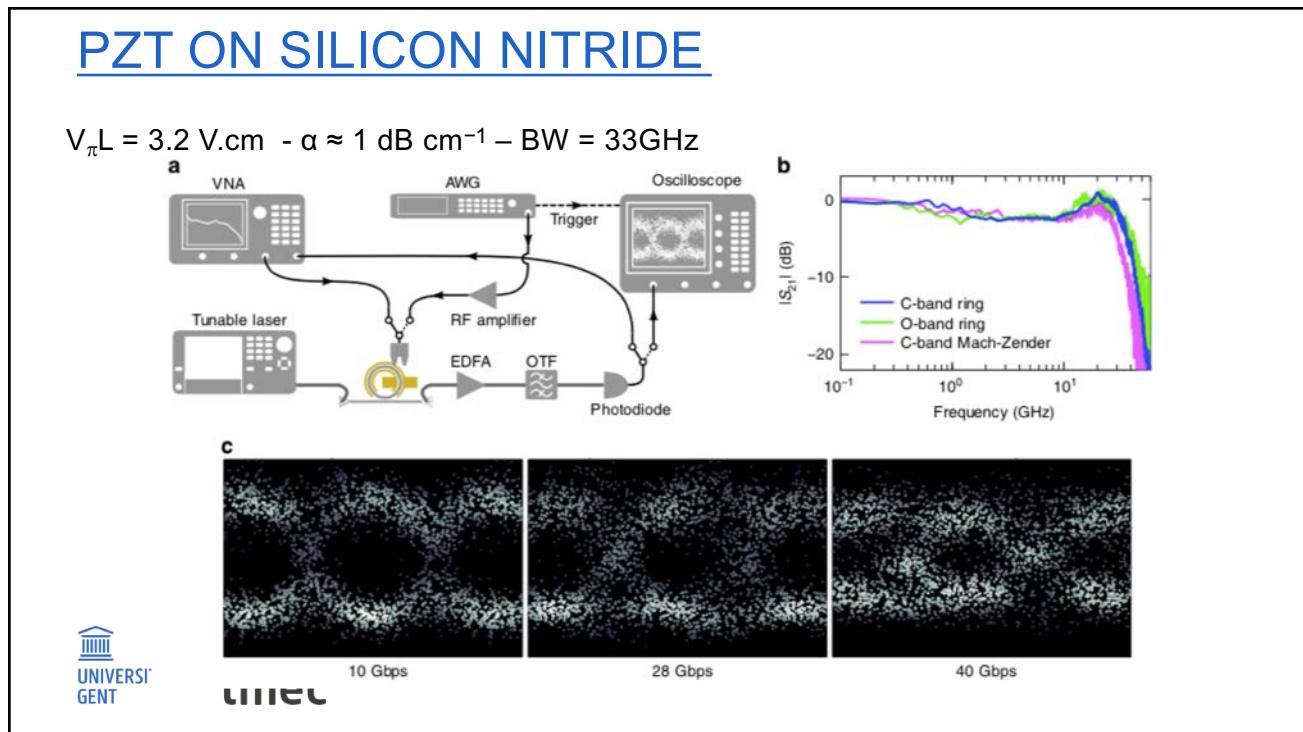
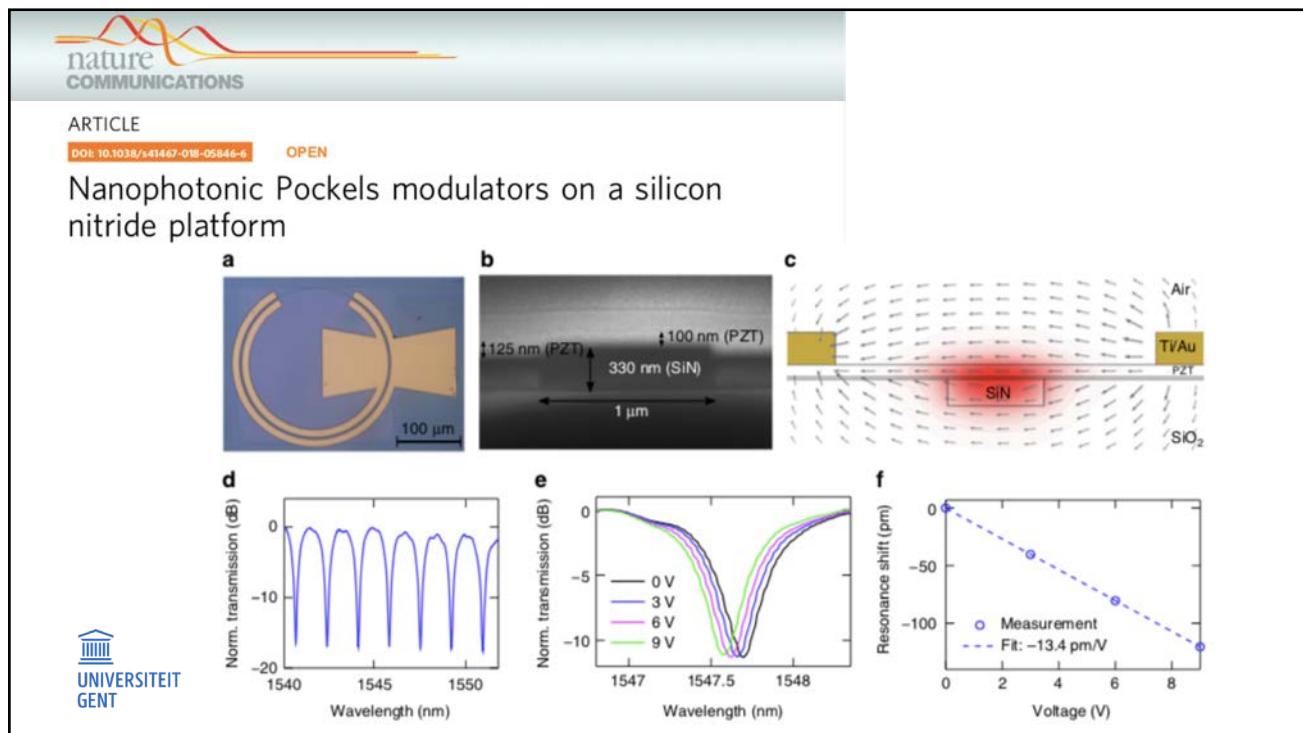
ELECTRONIC-PHOTONIC CO-INTEGRATION

- Co-design and co-integration of electronic ICs and photonic ICs for advanced TxRx (100G per wavelength & polarization)

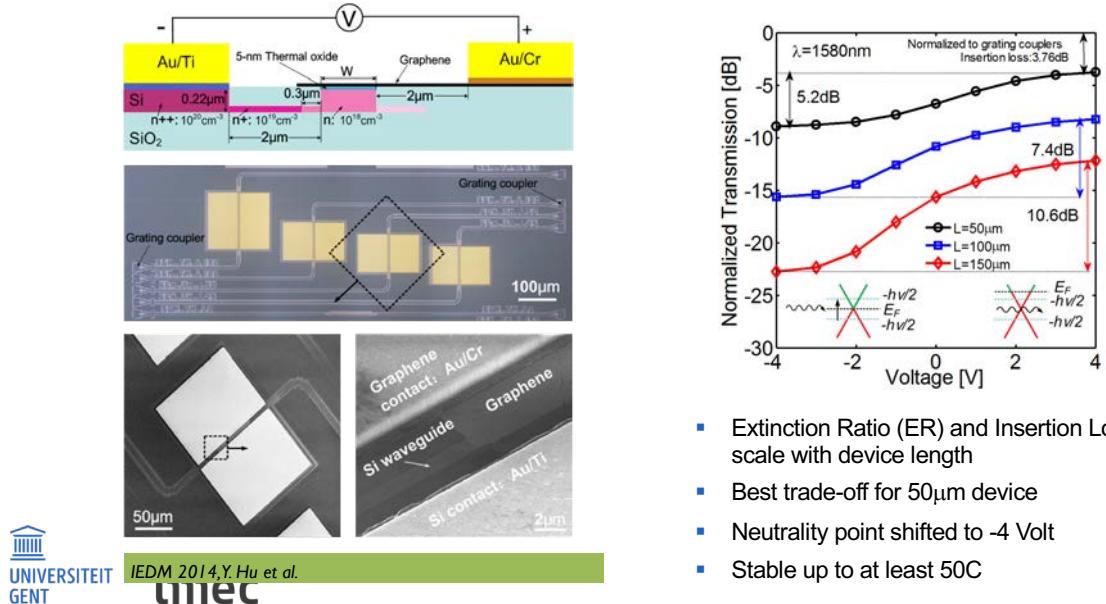


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GRAPHENE MODULATOR FABRICATION

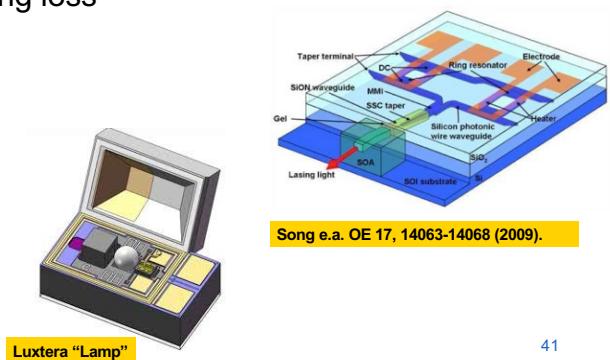


- Extinction Ratio (ER) and Insertion Loss (IL) scale with device length
- Best trade-off for 50 μm device
- Neutrality point shifted to -4 Volt
- Stable up to at least 50C

LASERS FOR SILICON PHOTONICS ?

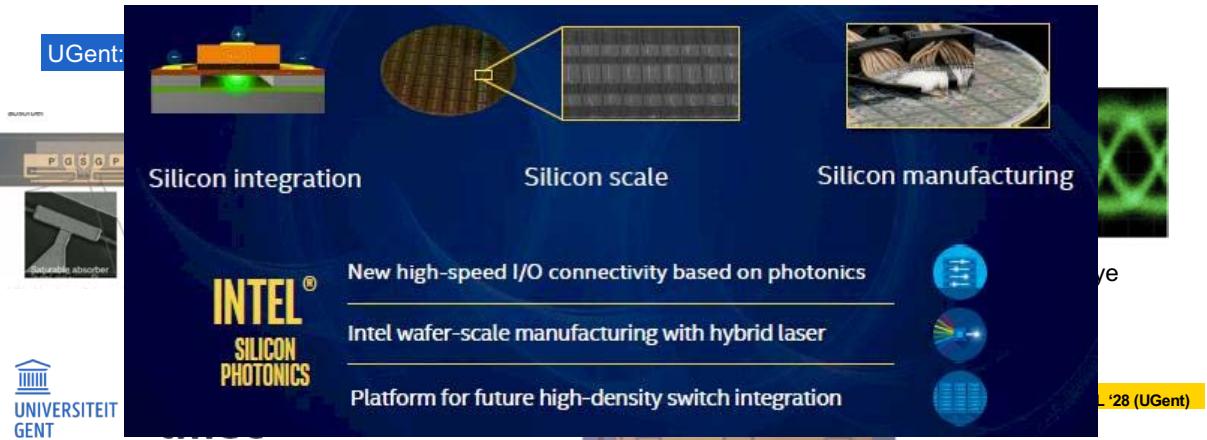
- Silicon has indirect bandgap: no light emission
- Need direct bandgap III-V semiconductors !
- Option 1: Off-chip laser
 - Most mature solution
 - Compatible with high temperature operation
 - Limited flexibility, not scalable, coupling loss
- Option 2: Flip-Chip
 - Prefabricated, pretested laser diode
 - Mature
 - Limited flexibility, limited scalability

Integration ??

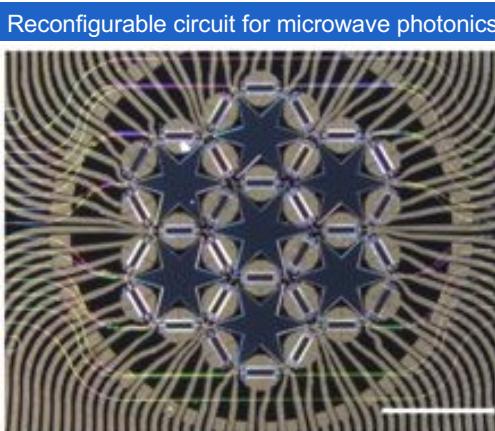


LASERS FOR SILICON PHOTONICS: MANY OPTIONS

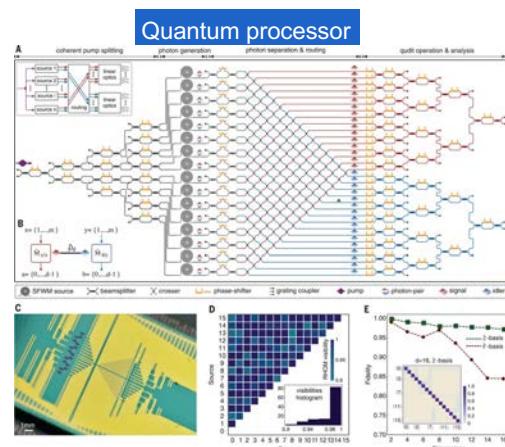
- Option 3: Wafer bonding (heterogeneous integration)
- Rapidly maturing
- Very versatile (different materials, different device structures ...)



TOWARDS LARGER DEGREE OF INTEGRATION



D. Perez, Nat. Comm. 8 (2017)
(Valencia)



J. Wang et al., Science (2018)
(Glasgow et al)

RESEARCH INFORMATION PROCESSING & COMPUTING

PROGRAMMABLE PHOTONIC INTEGRATED CIRCUITS

Develop general-purpose photonic ICs

- Mesh topologies (MZI, rings, lateral leakage)
- Distributed phase tuners and power monitors
- Scalable control algorithms

Software → Electrical Wiring → In-circuit Monitors → Outputs Monitors

heaters

In 1, In 2, In 3, In 4

D11, D12, D13, D21, D22

$\Delta\phi$

unperturbed waveguide, guided wave, lateral leakage

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PLASMONICS FOR SCALING DOWN BUILDING BLOCKS ?

a

Au, SiO_2 , $\lambda = \lambda_{\text{res}}$, $\lambda_r = \lambda_{\text{res}}$, SPPs, Photonic mode, 1 μm

b

Radius R , $d_{\text{Au-Si}} \approx 70 \text{ nm}$, $w_{\text{slot}} \approx 70 \text{ nm}$, Buried Si-WG, Pt contrast

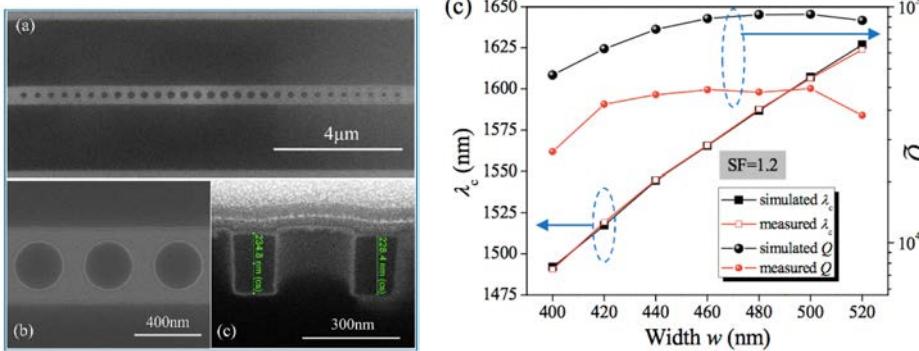
c

Transmittance (dB), Wavelength (μm), IL $\approx 2.5 \text{ dB}$, ER $\approx 10 \text{ dB}$, Q ≈ 30 , $R = 1,030 \text{ nm}$, $R = 1,080 \text{ nm}$

Leuthold group, Nature, 556: 483-486 (ETHZ)

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PHOTONIC CRYSTAL DEVICES



Photonic wire cavities fabricated using 300mm immersion litho

- Oxide cladding
- Very good match simulation vs. design, on-par with state-of-art ebeam ($Q > 1E6$)
- Very good uniformity over wafer
- Starting point for active devices (e.g. slow light modulators, switches ...)



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Xie e.a, JLT 2014

SILICON PHOTONICS – SUMMARY

- Silicon Photonics rapidly maturing:
 - All basic building blocks developed
 - Widely available from commercial foundries and through multi-project wafer services
- Current research focusses on:
 - Integration with new materials for enhancing functionality
 - Exploiting large scale integration for new applications
- Perfect match with EU-FET SPICE objectives !



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GROUP



ACKNOWLEDGMENTS – ALL GROUP MEMBERS



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Prof. Dries Van Thourhout
PHOTONICS RESEARCH GROUP

E dries.vanthourhout@ugent.be
T +32 9 264 34 38

www.photonics.intec.ugent.be

Ghent University
 @DThourhout
 Ghent University

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